

Deposit metal film on a Substrate.

-205

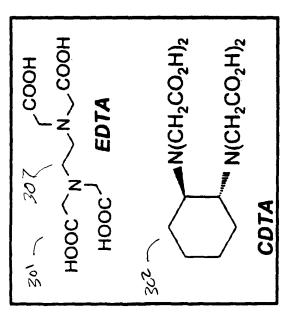
Deposit photo resist on the metal film and pattern Photoresist to expose undesired Portions of the metal film.

-210

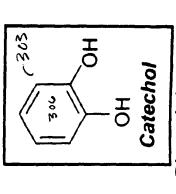
Use a chelating agent to remove the undesired Portion of the metal film.

-215

Fig. 2

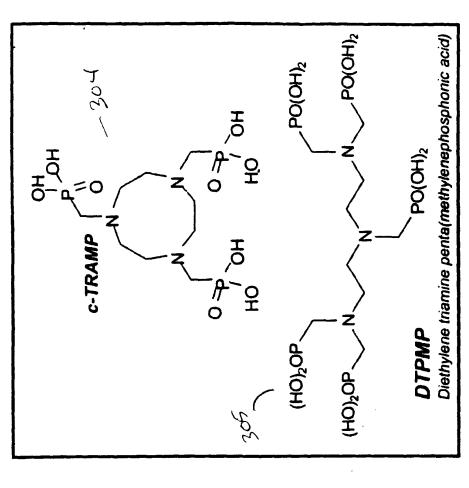


Carboxylic acid based



Phenol derivatives

Fig. 38



Phosphonic acid based

F19.3C

Fig. 4

film.